



GELLER MICROANALYTICAL LABORATORY

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Certified to ISO-9001 and 17025

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ION SPUTTER STANDARDS

Geller MicroAnalytical Laboratory offers ion sputter standards that are manufactured specifically for calibrating sputter ion guns. Thin films of SiO₂, Si₃N₄, and Ta₂O₅ are available. Special orders will be considered.

Silicon Dioxide

Silicon wafers (4") with thin films of silicon dioxide are currently available with the following nominal thicknesses and uniformities:

Thickness (Å)	Uniformity (±Å)	Price
220	2.3	\$975
230	2.3	\$975
500	25	\$495
1006	11	\$975
1029	11	\$975

Silicon Nitride

781Å stoichiometric Silicon Nitride (CVD) thin films deposited on a ~1 X 3 cm piece of silicon wafer are \$300.00.

Tantalum Pentoxide

Films of tantalum pentoxide are anodically grown on thin tantalum foil. The standards are ~ 37 X 37 mm and cost \$300.00 with a thicknesses of 555 or 593 ±20Å and 1120 ±40Å. The standards are measured (using electron beam excited x-ray analysis) against the NPL (NIST counterpart in the U.K.) .

Nickel/Chromium

12 alternating layers of approximately 50nm each over silicon. The size is 1 X 3 cm. \$600.00. See data sheet.

Please check for new additions. All items subject to availability.